CLAIMS

1. (Previously Presented) Method for the production of a glazing provided with a multilayer coating, said multiplayer coating being deposited on a glass substrate by cathodic sputtering at reduced pressure, characterised in that at least a first transparent dielectric layer is deposited on the substrate followed by the deposit of a functional layer of an Ag-based infrared reflective material, that in an atmosphere containing 20% oxygen at maximum, deposited on said functional layer is a first protective layer with a geometric thickness of 3 nm at maximum and composed of a material, of which the electronegativity different from oxygen is less than 1.9 and of which the electronegativity value is less than that of said infrared reflective material, followed by the deposit, in an atmosphere containing 50% oxygen at maximum, of a second protective layer, adjoining the first protective layer, with a geometric thickness of 7 nm at maximum and composed of a material, of which the electronegativity difference from oxygen is greater than 1.4, and that at least a second transparent dielectric layer is then deposited.

2 - 3. (Cancelled)

4. (Previously presented) Method according to Claim 1, characterised in that the electronegativity value of the material of the first protective layer is at least 0.05 less than that of the infrared reflective material.

5. (Previously presented) Method according to Claim 1, characterised in that the material of the second protective layer has a lower electronegativity value than the electronegativity value of the material of the first protective layer.

6-11. (Cancelled)

12. (Previously presented) Method according to Claim 1, characterised in that the second protective layer is deposited in a thickness in the range of between 2 nm and 6 nm.

13-18. (Cancelled)

19. (Previously presented) Method according to Claim 1, characterised in that at least two functional layers based on an infrared reflective material are deposited, each followed by the deposit of first and second protective layers, and in that at least one intermediate dielectric layer is deposited between said functional layers.

20. (Previously presented) Method according to Claim 1, characterised in that a final titanium-based protective layer is deposited to terminate the multilayer coating.

21. (Previously presented) Method for the production of a bent or toughened glazing provided with a multilayer coating, characterised in that a coated substrate obtained by the method according to Claim 1 is then subjected to a bending or toughening operation.

22. (Withdrawn) Glazing provided with a multilayer coating, characterised in that it comprises a glass substrate, on which is deposited at least one functional layer based on an infrared reflective material, the functional layer or at least one of the functional layers being enclosed by at least one transparent dielectric layer, and that on its face opposite the substrate and directly in contact therewith, said functional layer is covered by a first protective layer with a geometric thickness of 3 nm at maximum and composed of a metal- or semi-metal-based material in metal, nitrided or sub-oxidised form, of which the electronegativity difference from oxygen is less than 1.9 and of which the electronegativity value is less than that of the infrared reflective material, followed by a second protective layer with a geometric thickness of 7 nm at maximum and composed of a material based on metal or semi-metal in substantially totally oxidised form, of which the electronegativity difference from oxygen is greater than 1.4 and which is different from the material of the transparent dielectric layer directly adjoining it.

23. (Cancelled)

24. (Withdrawn) Glazing according to Claim 22, characterised in that the or at least one of the first protective layers is/are composed of a material, of which the electronegativity difference from oxygen is less than 1.8 and preferably less than 1.7.

25. (Withdrawn) Glazing according to Claim 22, characterised in that the or at least one of the second protective layers is/are composed of a material, of which the electronegativity difference from oxygen is greater than 1.6 and preferably greater than 1.8.

26. (Withdrawn) Glazing according to Claim 22, characterised in that the electronegativity value of the material of the or at least one of the first protective layers is at least 0.05 less than that of the infrared reflective material adjoining it.

27. (Withdrawn) Glazing according to Claim 22, characterised in that the material of the or at least one of the second protective layers has a lower electronegativity value than the electronegativity value of the material of the first protective layer adjoining it.

28. (Withdrawn) Glazing according to Claim 27, characterised in that the material of the or at least one of the second protective layers has an electronegativity value at least 0.1, and preferably at least 0.2, less than the electronegativity value of the material of the first protective layer adjoining it.

29. (Withdrawn) Glazing according to Claim 22, characterised in that the or at least one of the functional layers is/are Ag-based, and that said first protective layer or layers is/are based on an alloy of Ni and Cr, and said second protective layer or layers is/are formed from titanium oxide.

30-32. (Cancelled)

33. (Withdrawn) Bent or toughened glazing provided with a multilayer coating, characterised in that it comprises a glass substrate, on which is deposited at least one functional layer based on an infrared reflective material, the functional layer or at least one of the functional

layers being enclosed by at least one transparent dielectric layer, and that on its face opposite the substrate and directly in contact therewith, said functional layer is covered by a first protective layer with a geometric thickness of 3 nm at maximum and composed of a metal- or semi-metal-based material in oxidised or sub-oxidised form, of which the electronegativity difference from oxygen is less than 1.9, followed by a second protective layer with a geometric thickness of 7 nm at maximum and composed of a material based on metal or semi-metal in substantially totally oxidised form, of which the electronegativity difference from oxygen is greater than 1.4 and which is different from the material of the transparent dielectric layer directly adjoining it.

34. (Cancelled)

35. (Withdrawn) Glazing according to Claim 33, characterised in that the or at least one of the first protective layers is/are composed of a material, of which the electronegativity difference from oxygen is less than 1.8 and preferably less than 1.7.

36. (Withdrawn) Glazing according to Claim 33, characterised in that the or at least one of the second protective layers is/are composed of a material, of which the electronegativity difference from oxygen is greater than 1.6 and preferably greater than 1.8.

37. (Withdrawn) Glazing according to Claim 33, characterised in that the electronegativity value of the material of the or at least one of the first protective layers is less than that of the infrared reflective material adjoining it, and preferably by at least 0.05.

38. (Withdrawn) Glazing according to Claim 33, characterised in that the material of the or at least one of the second protective layers has a lower electronegativity value than the electronegativity value of the material of the first protective layer adjoining it.

39. (Withdrawn) Glazing according to Claim 38, characterised in that the material of the or at least one of the second protective layers has an electronegativity value at least 0.1, and preferably at least 0.2, less than the electronegativity value of the material of the first protective layer adjoining it.

40. (Withdrawn) Glazing according to Claim 33, characterised in that the functional layer is Ag-based, and that said first protective layer or layers is/are based on an alloy of Ni and Cr, and said second protective layer or layers is/are formed from titanium oxide, and that at least one of the dielectric layers contains a zinc-based oxide, preferably an oxide based on a zinc- tin alloy.

41-48. (Cancelled)

49. (Previously Presented) Method according to Claim 1, characterised in that the first protective layer is composed of a material, of which the electronegativity difference from oxygen is less than 1.8.

50. (Previously Presented) Method according to Claim 1, characterised in that the first protective layer is composed of a material of which the electronegativity difference from oxygen is less than 1.7.

51. (Previously Presented) Method according to Claim 1, characterised in that the second protective layer is composed of a material, of which the electronegativity difference from oxygen is greater than 1.6.

52. (Previously Presented) Method according to Claim 1, characterised in that the second protective layer is composed of a material, of which the electronegativity difference from oxygen is greater than 1.8.

53. (Previously Presented) Method according to Claim 5, characterised in that the material of the second protective layer has an electronegativity value at least 0.1 less than the electronegativity value of the material of the first protective layer.

54. (Previously Presented) Method according to Claim 5, characterised in that the material of the second protective layer has an electronegativity value at least 0.2, less than the electronegativity value of the material of the first protective layer.

55. (Previously Presented) Method according to Claim 1, characterised in that the first protective layer is NiCr-based.

56. (Previously Presented) Method according to Claim 1, characterised in that the first protective layer is based on an NiCr 80/20 alloy.

57. (Previously Presented) Method according to Claim 1, characterised in that the material of the second protective layer is selected from titanium, aluminium or tantalum.

58. (Previously Presented) Method according to Claim 1, characterised in that the material of the second protective layer is titanium.

59. (Previously Presented) Method according to Claim 1, characterised in that the first protective layer is deposited in a thickness in the range of between 0.5 nm and 2.5 nm.

60. (Previously Presented) Method according to Claim 1, characterised in that the first protective layer is deposited in a thickness in the range of between 0.5 nm and 2 nm.

61. (Previously Presented) Method according to Claim 1, characterised in that the first protective layer is deposited in a thickness in the range of between 0.6 nm and 1.5 nm.

62. (New) Method according to Claim 1, characterised in that the second protective layer is deposited in an atmosphere containing a maximum of 20% oxygen.

63. (New) Method according to Clai 1, characterised in that the second protective layer is deposited in an atmosphere containing a maximum of 10% oxgen.